10696782_CLS.txt Most Frequently Occurring Classifications of Patents Returned From A Search of 10696782 on February 15, 2005

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Original Classifications

8 250/492.21

2 250/492.2

2 376/105

2 438/514
Cross-Reference Classifications
4 250/398
3 250/397
3 250/492.2
2 250/281
2 250/305
                   250/423R
                   250/492.21
                  313/361.1
313/362.1
315/111.41
315/505
376/120
430/599
                   430/600
                   510/276
Combined Classifications
10 250/492.21
5 250/492.2
4 250/397
4 250/398
3 250/423R
2 204/252
2 204/296
2 250/281
2 250/305
2 250/442.11
2 313/359.1
                  313/359.1
313/361.1
313/362.1
315/111.41
315/111.81
315/505
376/105
376/120
430/567
430/567
430/569
430/600
438/514
438/766
510/224
510/276
                   313/359.1
                   510/276
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10696782_CLSTITLES.txt

Titles of Most Frequently Occurring Classifications of Patents Returned From A Search of 10696782 on February 15, 2005

```
(8 OR, 2 XR)
250 : RADIANT ENERGY
10 250/492.21
          Class
          250/492.1
                          IRRADIATION OF OBJECTS OR MATERIAL
                          .Irradiation of semiconductor devices
          250/492.2
          250/492.21
                          ..Ion bombardment
          192.2 (2 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION 07
 5 250/492.2
                          IRRADIATION OF OBJECTS OR MATERIAL .Irradiation of semiconductor devices
          250/492.2
          97 (1 OR, 3 XR)
Class 250: RADIANT ENERGY
          250/396R
                          WITH CHARGED PARTICLE BEAM DEFLECTION OR
                               FOCUSSING
          250/397
                          .With detector
                    (0 OR, 4 XR)
          Class 250: RADIANT ENERGY
          250/396R
                          WITH CHARGED PARTICLE BEAM DEFLECTION OR
                               FOCUSSING
          250/398
                           .With target means
          23R (1 OR, 2 XR)
Class 250: RADIANT ENERGY
 3 250/423R`
          250/423R
                          ION GENERATION
                     (1 \text{ OR}, 1 \text{ XR})
   204/252
                   204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
          Class
          204/193
204/194
                          APPARATUS
                          .Electrolytic
                          ..Cells
          204/242
          204/252
                          ...Diaphragm type
 2 204/296
                     (1 OR, 1 XR)
          Class
                   204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
          204/193
204/194
                          APPARATUS
                          .Electrolytic
                          ..Elements
          204/279
          204/295
                          ...Diaphragms
          204/296
                          ....Organic
                   (0 OR, 2 XR)
250 : RADIANT ENERGY
 2 250/281
          Class
          250/281
                          IONIC SEPARATION OR ANALYSIS
          05 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
   250/305
          250/305
                          ELECTRON ENERGY ANALYSIS
                   (1 OR, 1 XR)
250 : RADIANT ENERGY
 2 250/442.11
          class
                          INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED
          250/306
                                PARTICLES
          250/440.11
                          .Analyte supports
          250/442.\overline{11}
                           .. With object moving or positioning means
                   (1 OR, 1 XR)
313 : ELECTRIC LAMP AND DISCHARGE DEVICES
   313/359.1
          Class
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10696782_CLSTITLES.txt
         313/359.1
                         WITH POSITIVE OR NEGATIVE ION ACCELERATION
                   (0 OR, 2 XR)
  313/361.1
                  313 : ELECTRIC LAMP AND DISCHARGE DEVICES
         Class
         313/359.1
                         WITH POSITIVE OR NEGATIVE ION ACCELERATION
         313/361.1
                         .Means for deflecting or focusing
                   (0 OR, 2 XR)
2 313/362.1
                  313 : ELECTRIC LAMP AND DISCHARGE DEVICES
         Class
         313/359.1
                         WITH POSITIVE OR NEGATIVE ION ACCELERATION .Supplying ionizable material (e.g., gas or
         313/362.1
                            vapor)
  315/111.41
                   (0 \text{ OR}, 2 \text{ XR})
         Class
                         ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
         315/111.01
                         DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
                               SUPPLY TO THE DISCHARGE SPACE
         315/111.21
                         .Plasma generating
         315/111.41
                         ..With magnetic field
2 315/111.81
                   (1 \text{ OR}, 1 \text{ XR})
                  315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
         Class
         315/111.01
                         DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
                         SUPPLY TO THE DISCHARGE SPACE .Electron or ion source
         315/111.81
  315/505
                   (0 \text{ OR}, 2 \text{ XR})
         Class
                  315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
         315/500
315/501
                         HIGH ENERGY PARTICLE ACCELERATOR TUBE .Magnetic field acceleration means
         315/505
                         ..Linear accelerator (Linac)
2 376/105
                   (2 OR, 0 XR)
                  376 :
         Class
                          INDUCED NUCLEAR REACTIONS:
                                                          PROCESSES,
                           SYSTEMS, AND ELEMENTS
         376/100
                         NUCLEAR FUSION
                         .Inertial confinement (e.g., nuclear explosive)
         376/102
                         .. Particle beam irradiation (excluding photons)
         376/105
                   (0 \text{ OR}, 2 \text{ XR})
  376/120
         Class
                  376 : INDUCED NUCLEAR REACTIONS: PROCESSES,
                           SYSTEMS, AND ELEMENTS
                         NUCLEAR FUSION
         376/100
         376/120
                         .Including bunched particle beam
2 430/567
                   (1 \text{ OR}, 1 \text{ XR})
         Class
                  430 :
                          RADIATION IMAGERY CHEMISTRY: PROCESS,
                         COMPOSITION, OR PRODUCT THEREOF RADIATION SENSITIVE PRODUCT
         430/495.1
         430/564
430/567
                         .Silver compound sensitizer containing
                         ..Silver compound having specified crystal
                            form, habit, particle size or particle size distribution
2 430/599
                   (0 \text{ OR}, 2 \text{ XR})
                          RADIATION IMAGERY CHEMISTRY: PROCESS,
         Class
                  430 :
                           COMPOSITION, OR PRODUCT THEREOF
                         RADIATION SENSITIVE PRODUCT
         430/495.1
         430/564
                         .Silver compound sensitizer containing
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10696782_CLSTITLES.txt
            430/599
                             .. Hypersensitizing or latensifying ingredient
                                containing
  2 430/600
                       (0 \text{ or, } 2 \text{ XR})
                             RADIATION IMAGERY CHEMISTRY: PROCESS,
            Class
                               COMPOSITION, OR PRODUCT THEREOF
            430/495.1
                             RADIATION SENSITIVE PRODUCT
            430/564
                             .Silver compound sensitizer containing
            430/599
                             .. Hypersensitizing or latensifying ingredient
                                 .
containing
                             ...Heterocyclic N, O, S, Se, or Te compound
            430/600
                                containing
  2 438/514
                       (2 OR, 0 XR)
            Class
                            SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
            438/510
                             INTRODUCTION OF CONDUCTIVITY MODIFYING DOPANT
                                 INTO SEMICONDUCTIVE MATERIAL
            438/514
                             .Ion implantation of dopant into semiconductor
                                region
  2 438/766
                       (1 \text{ OR}, 1 \text{ XR})
            Class
                     438 :
                             SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
            438/758
                             COATING OF SUBSTRATE CONTAINING SEMICONDUCTOR
                                   REGION OR OF SEMICONDUCTOR SUBSTRATE
            438/765
                             .By reaction with substrate
                             ..Implantation of ion (e.g., to form ion amorphousized region prior to selective oxidation,
            438/766
reacting
                                with substrate to form insulative region, etc.)
  2 510/224
                       (1 OR, 1 XR)
                             CLEANING COMPOSITIONS FOR SOLID SURFACES
            Class
                     510 :
                               AUXILIARY COMPOSITIONS THEREFOR, OR PROCESSES
                                                                                        0F
                               PREPARING THE COMPOSITIONS
            510/108
                             CLEANING COMPOSITIONS OR PROCESSES OF PREPARING
                                     (E.G., SODIUM BISULFATE COMPONENT, ETC.)
                             .For cleaning a specific substrate or removing a specific contaminant (e.g., for smoker's pipe, etc.)
            510/109
                             ... For equipment used in processing, handling,
            510/218
                                  storing, or serving edible product (e.g., dairy or
brewery
                                  equipment, household utensils, etc.)
            510/220
                             ...For use in automatic dishwasher
            510/224
                             ....Solid, shaped article (e.g., tablet,
                                briquette, pellet, etc.)
                       (0 OR, 2 XR)
  2 510/276
           Class
                             CLEANING COMPOSITIONS FOR SOLID SURFACES,
                               AUXILIARY COMPOSITIONS THEREFOR, OR PROCESSES
                                                                                        OF
                               PREPARING THE COMPOSITIONS
                            CLEANING COMPOSITIONS OR PROCESSES OF PREPARING

(E.G., SODIUM BISULFATE COMPONENT, ETC.)

.For cleaning a specific substrate or removing
  a specific contaminant (e.g., for smoker's pipe, etc.)

..For textile material (e.g., laundry
            510/108
           510/109
            510/276
```

detergent, etc.)